

## **ABSTRACT OF THE DISCLOSURE**

~~The invention provides~~ method of etching and cleaning objects contained in a vessel, ~~including:~~ includes etching the objects by providing etching solution into the vessel; forcing out ~~exiting~~ the etching solution from the vessel by providing pressurized gas into the vessel; cleaning the objects by providing cleaning solution into the vessel; and draining the cleaning solution from the vessel. By forcing out ~~exiting~~ the etching solution with a pressurized gas such as nitrogen gas, there is no density difference of the etching solution ~~through-out~~ in contact with the objects, leading to uniform etching of the objects.